THIN FILM MATERIALS · TECHNICAL PLANNING REFERENCE

Magnesium Oxide Sputtering Target

Typical Specification Sheet · For preliminary RFQ discussion

Planning reference only. Illustrative values are not a batch CoA or guaranteed acceptance limits; order-specific requirements and actual batch documentation govern.

MgO	99.9910%	90 ppm	PASS
Material	Illustrative matrix	Illustrative impurities	Closed arithmetic

Reference product definition

Reference grade	4N nominal planning grade (99.99 wt%)
Order-specific scope	Geometry, finished dimensions, tolerances, bonding/backing, inspection and acceptance criteria are per approved drawing and quotation.

Closed illustrative composition model

The matrix balance and listed illustrative impurities form one closed mass-basis model. Basis: wt%, total mass basis.

Constituent	Illustrative wt%	Equivalent ppm	Role
MgO	**99.9910**	—	matrix balance
Si	0.0020	20	illustrative typical impurity
Fe	0.0015	15	illustrative typical impurity
Ca	0.0015	15	illustrative typical impurity
Al	0.0015	15	illustrative typical impurity
Na	0.0005	5	illustrative typical impurity
Ni	0.0005	5	illustrative typical impurity
Cu	0.0005	5	illustrative typical impurity
Other	0.0010	10	illustrative typical impurity
Total impurities	**0.0090**	**90**	**arithmetic checked**
COMPOSITION TOTAL	**100.0000**	—	**PASS**

ARITHMETIC VALIDATION: matrix 99.9910 wt% + illustrative impurities 0.0090 wt% = 100.0000 wt%. Individual impurity sum = 90 ppm. ALL CHECKS PASS.

Information to include in an RFQ

Target geometry and drawing/revision · finished dimensions and tolerances · required purity/composition basis · controlled impurities · planar or rotary configuration · bonding/backing requirement · quantity · inspection and document requirements.

Use this sheet only for early engineering discussion. Request an order-specific specification and the actual batch CoA before material acceptance or use.